What is claimed is

1. An optical information recording medium, comprising:

a record layer which is formed on a substrate and cause a reversible change between an amorphous phase and a crystalline phase by laser beam irradiation, the change being optically detectable;

a first dielectric layer which is formed between the record layer and the substrate, and mainly composed of niobium oxide or silicon dioxide; and

a second dielectric layer which is formed between the record layer and the first dielectric layer, and mainly composed of titanium oxide.

2. The optical information recording medium according to claim 1, wherein the second dielectric layer contains 51mol% or more of titanium oxide.

3. The optical information recording medium according to claim 1, wherein the second dielectric layer has a thickness in the range of 10 to 40 nm.

4. The optical information recording medium according to claim 1, wherein a second record layer is

provided on the opposite side to the record layer from the substrate.

5. The optical information recording medium according to claim 1, wherein a reflection layer is provided between the second dielectric layer and the record layer.

6. A method for manufacturing an optical information recording medium, comprising the steps of:

forming a first dielectric layer mainly composed of niobium oxide or silicon dioxide on a substrate;

forming a second dielectric layer mainly composed of titanium oxide on the first dielectric layer formed; and

forming a record layer on the second dielectric layer formed, on which a reversible and optically detectable change can be made to be between an amorphous phase and a crystalline phase by laser beam irradiation.

7. The method for manufacturing an optical information recording medium according to claim 6, wherein the second dielectric layer contains not less than 51mol% of titanium oxide.

8. The method for manufacturing an optical

information recording medium according to claim 6, wherein the second dielectric layer is formed in a thickness of 10 to 40 nm as a transmittance adjustment layer.

9. The method for manufacturing an optical information recording medium according to claim 6, wherein when the first dielectric layer, the second dielectric layer and the record layer are formed on a substrate, water and oxygen are removed from the substrate before the formation of the first dielectric layer or the second dielectric layer.

10. The method for manufacturing an optical information recording medium according to claim 6, further comprising a step of forming a second record layer that causes a reversible change from an amorphous phase to a crystalline phase, which is optically detectable by laser beam irradiation.

11 The method for manufacturing an optical information recording medium according to claim 6, comprising a step of forming a reflection layer between the second dielectric layer and the record layer.